

COATING SYSTEMS FOR THIN-FILM PV

SCALA | VISS | GC120V | PIA|nova | XENIA

OUR STORY. OUR EXPERIENCE.

VON ARDENNE provides advanced PVD coating equipment for all scales of production, from laboratory tasks to high-volume manufacturing. Our company was founded in 1991 as a spin-off of the Manfred von Ardenne Research Institute in Dresden, Germany.

With more than 55 years of experience in vacuum coating and over 40 years in magnetron sputtering, VON ARDENNE is one of the leading providers of equipment and technologies for PVD thin-film technology and vacuum processing.

We have installed more than 150 systems for customers within the thin-film photovoltaics industry, which is an equivalent of an installed manufacturing capacity of more than five gigawatts. This makes VON ARDENNE the market leader in production equipment for thin-film PV. The reliability and productivity of these systems are well proven in the PV industry.

Currently, however, the importance of large-area formats and form factors in general is shifting in the thin-film photovoltaics industry. Typically, modules for CIGS or CdTe based cells are smaller in size as compared to Si-wafer based modules due to certain historical and technical reasons, such as the cell interconnection.

VON ARDENNE is quite familiar with the development and manufacturing of larger machines, as the company has been providing coating equipment for large-area coating applications that require much wider dimensions. Moreover, we provide systems that are necessary prior to large-scale production – such as the SCALA LabX for laboratory tests or the vertical inline sputter system VISS for layer stack development under pilot production conditions.

We have supplied vacuum coating equipment for the PV industry since 2004, primarily for thin-film coatings on glass. One of the most versatile coating systems VON ARDENNE offers for these applications is the PIA|nova®. This is a horizontal glass coating system for depositing thin films using sputtering technology. Its standardized subcomponents enable custom-made configurations. Three process chamber designs are available that allow processes without heating or with heating of up to 400 °C.

The VON ARDENNE GC120VCR is a vertical in-line coating system for the deposition of oxide thin-film multilayer systems and metal layers on flat substrates. The system uses carriers for the substrate transport and enables also custom-made configurations based on standardized subcomponents.

Based on the mentioned experience, VON ARDENNE has developed the XENIA. The coater is a very wide horizontal sputtering machine and can therefore process multiple substrates at the same time. It is especially suited for high-productivity applications at very low costs. All our coaters are equipped with the field-proven and leading VON ARDENNE sputtering technology.

It is VON ARDENNE's mission is to continue to be the key equipment manufacturers within the photovoltaics industry. Therefore, we focus on high-efficiency and leading PV technologies and commit ourselves to the cost-effective use of solar power.

MARKET
LEADERSHIP
IN ADVANCED COATING EQUIPMENT FOR

**THIN-FILM
PHOTOVOLTAICS**
> 8 GW*

*INSTALLED MANUFACTURING CAPACITY

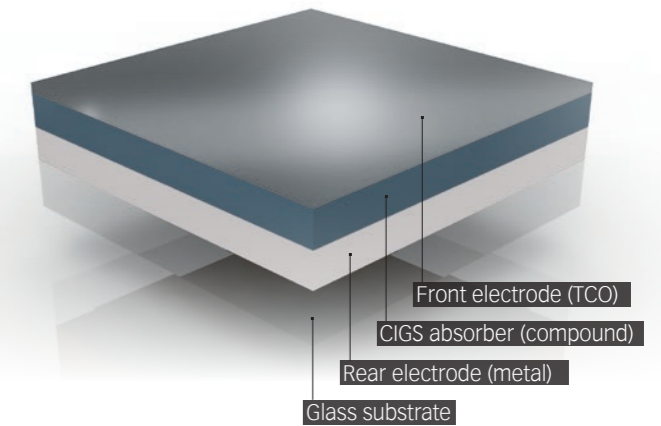
RANGE OF APPLICATIONS

CIGS-based thin-film solar cell modules represent the highest-efficiency alternative for large-scale, commercial thin-film solar cells. In the schematic illustration, you see a typical CIGS layer stack on glass.

In this design, the layers of the device are deposited onto a glass substrate. Sunlight enters through the top layer of the device (the transparent conducting oxide) and produces electrical current and voltage in the lower layers.

CIGS Thin-Film Photovoltaics

- i-ZnO, ZnO:Al based front contact layers
- CuGa and In precursor layer
- SiOxNy barrier layers and Mo metal back contact layers

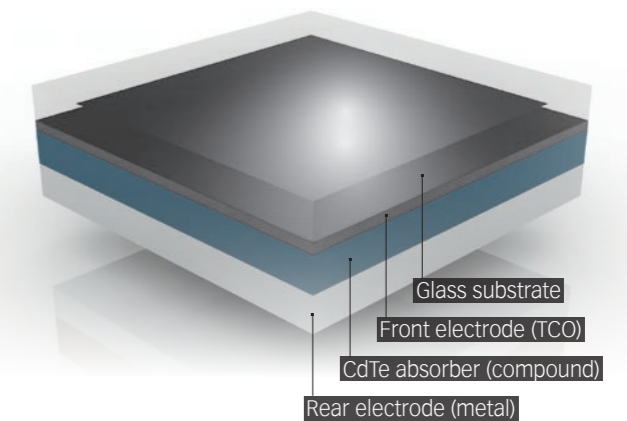


Solar cells based on cadmium telluride (CdTe) constitute the major segment of the global thin-film module production. Transparent conducting oxide (TCO) layers are translucent and highly conductive to transport current efficiently. Intermediate layers help in both the growth and electrical properties between the TCO and CdTe.

The CdTe film acts as the primary photoconversion layer and absorbs most visible light within the first micron of material. Together, these layers form an electric field that converts the absorbed light into current and voltage. A metal layer is deposited on the back to form electrical contacts.

CdTe Thin-Film Photovoltaics

- Metal back contact layers based on Al, Cr, Mo, NiV
- TCO and intermediate layers

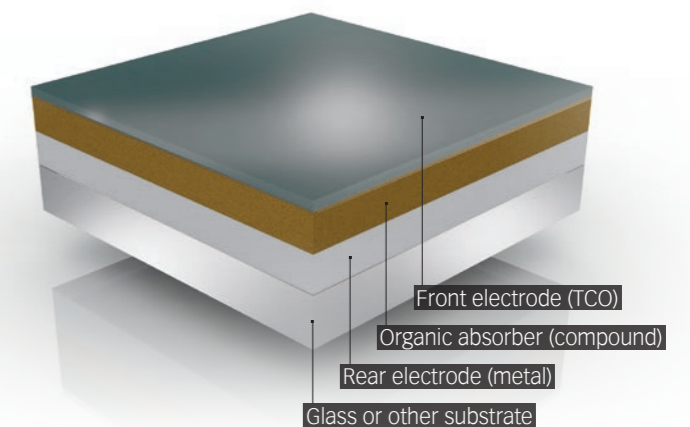


Organic photovoltaics is a rapidly emerging technology with an improving cell efficiency. Furthermore, this technology shows a promising initial lifetime and potential for roll-to-roll manufacturing processes.

Organic photovoltaics might be especially interesting for the building-integrated PV market because of the ability to make efficient transparent devices and the availability of absorbers in several different colors.

Organic Photovoltaics

- Deposition by sputtering and VTE



CORE TECHNOLOGY BASED ON A LONG TRADITION

INDUSTRY-PROVEN, RELIABLE AND ADVANCED SPUTTERING TECHNOLOGY

1 PROVEN MAGNETRON TECHNOLOGY

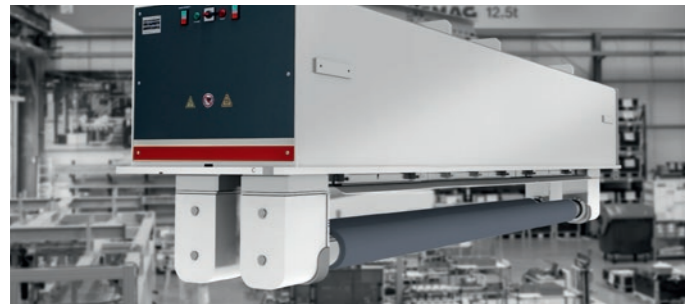
The main technology used for coating on VON ARDENNE equipment is magnetron sputtering. We develop and manufacture the necessary components such as magnetron sputtering sources in-house and have more than 40 years of experience with magnetron sputtering.

VON ARDENNE MAGNETRONS

VON ARDENNE magnetrons are available for a wide range of applications. Thanks to many years of experience gained from designing and installing advanced sputtering equipment, we can offer a complete portfolio of solutions from RF and AC to DC processes, planar to rotatable applications and even magnetrons with integrated turbopumps.



SSM/SSM-SSM Magnetrons

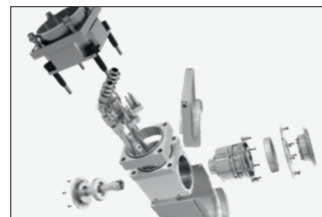


RSM/RSM-RSMT/RSMT Magnetrons



MAGNET BARS

All magnet bars and magnet systems are similar in mechanical design and therefore interchangeable.



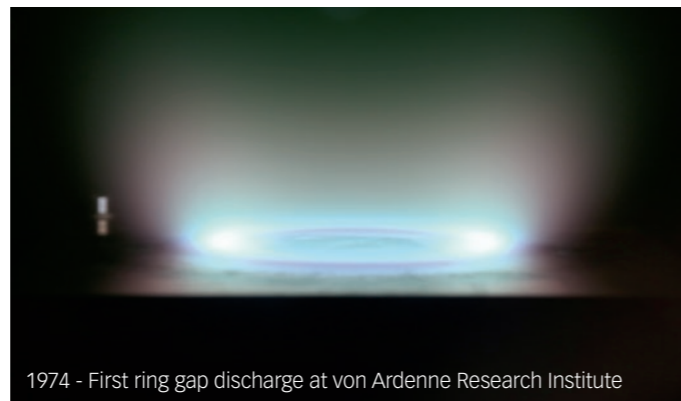
X-SERIES END BLOCKS

With our state-of-the-art X-Series end blocks, we offer both drop-in and cantilever solutions for our coating systems.



PROCESS CONTROL

The VON ARDENNE process control system VApocos2 controls the reactive magnetron sputtering of compound layers.



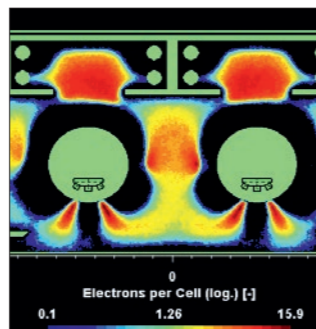
1974 - First ring gap discharge at von Ardenne Research Institute



WSM/WSMT Magnetrons

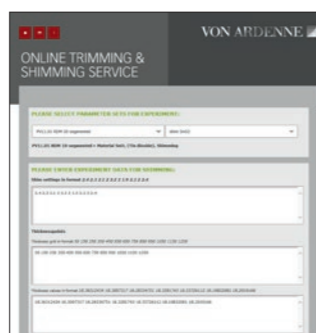


RDM/RDMT Magnetrons



DUAL ANODE SPUTTERING

Dual Anode Sputtering (DAS) is an industrially proven coating technology. It can be applied for highly-resistive target materials such as intrinsic tin oxide (i-ZnO). The DAS method guarantees a good availability of the anode as it is cleaned periodically, even when dielectrics are sputtered.



TRIMMING & SHIMMING

A web-based trimming and shimming software is available. It enables the quick optimization of the thickness uniformity of single layers. Upon request, an online adjustable magnet bar can be offered.

FEATURES AND BENEFITS OF VON ARDENNE EQUIPMENT

MODULAR, SCALABLE AND FLEXIBLE DESIGN BASED ON GERMAN ENGINEERING

2 INDIVIDUAL PROCESS CHAMBERS

The process chambers can be configured individually based on the flexible VON ARDENNE compartment system. They have a scalable design and can be configured according to the requirements of our customers. The components our systems are fitted with have proven in the industry for many years.

3 TRANSPORT SYSTEM

The substrate transport system used in our equipment can be either carrier-less or carrier-based depending on the process and the requirements of the customer. The customer can also choose between systems with a horizontal or a vertical substrate transport.

Furthermore, there are two drive modes, one for use in vacuum and one for operation under atmospheric pressure. The substrates can be transported either as a single item or as multiple items in a batch.

4 HEATING AND COOLING

HEATING CONTROL SYSTEM: The VON ARDENNE advanced heating control system is the first solution worldwide for the reliable and even heating of substrates before and during the coating process. The system is characterized by easy operation and helps increase the efficiency of the production process and lower operating costs. The reliable and quick setting of the substrate temperature within narrow tolerances and the high temperature uniformity shorten the ramp up time and minimize breakage and scrap.

The VON ARDENNE advanced heating control system is a standard component for heating treatment, e.g. in the coating systems PIA|nova®, GC120V and XENIA.

COOLING SYSTEM: The VON ARDENNE solution for the critical phase of the temperature treatment is our uniquely designed substrate cooling station that is positioned downstream the vacuum chambers. It cools by means of the air convection principle.

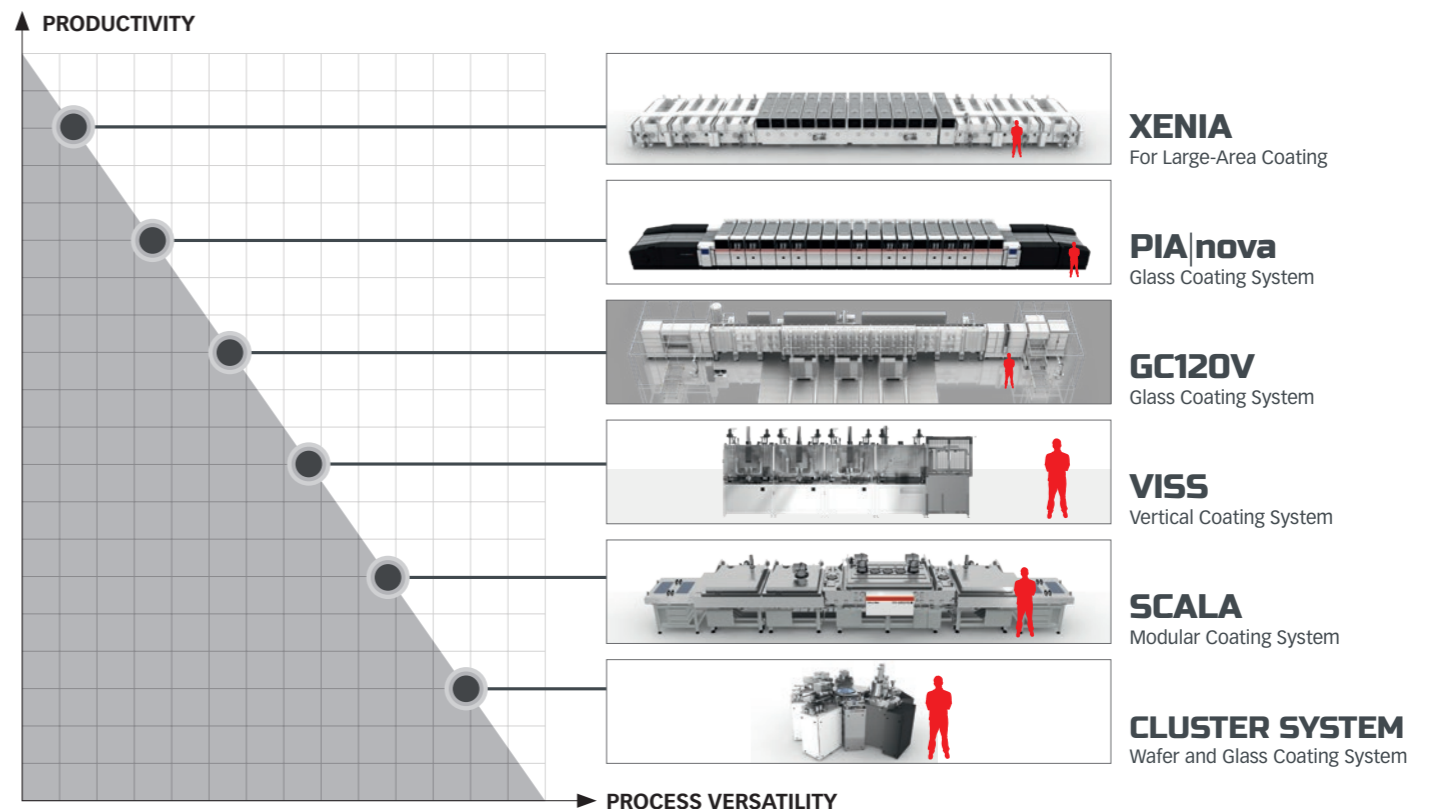
BENEFITS

- Quick setting of substrate temperature shortens ramp up time
- High temperature uniformity
- Reliable temperature control even
- Minimized glass consumption during conditioning
- Fast cool down of system in case of maintenance

5 SCALABILITY

VON ARDENNE provides advanced PVD coating equipment, key components and technology expertise for all scales of production, from laboratory tasks to high-volume manufacturing.

Our laboratory-scale coating systems and pilot production tools use the same key components as our systems for industrial production, however at a smaller scale. Thus, our customers can test their applications under laboratory conditions and save time when they scale their products up to a larger productivity or for mass production.



SCALA MODULAR COATING SYSTEM

FLEXIBLE TOOL FOR R&D PURPOSES OR PILOT PRODUCTION



The **SCALA** is a modular vacuum coating system with a carrier-based substrate transport. It is the perfect choice if you are looking for highly flexible production equipment with a small or medium throughput equipped with proven technology.

Thanks to its modular design, the **SCALA** can be configured according to your needs. We offer two basic configurations of the system.

The **SCALA LabX** is a single-ended tool for horizontal batch processing with or without load lock. It is ideally suited for process and application development at laboratory scale.

The **SCALA PilotX**, on the other hand, is designed for horizontal inline operation and therefore suitable for pilot production.



HIGH PROCESS FLEXIBILITY

The process chamber can be configured with planar or rotatable magnetrons. Ion pre-treatment or heating and cooling units are available upon request. All auxiliary chambers, like entry/exit, buffer and transport chamber, can be upgraded in a similar manner.

FLEXIBLE AND DYNAMIC DESIGN

The standardized subcomponents enable custom-made configurations with a high degree of flexibility. That means that the system can be adapted to new processes or requirements. Therefore, our customers are able to act very dynamically and to adapt to the evolution of their product.

OPTIONAL FEATURES

Substrate heating
Pre-treatment (e.g. Ion etching,...)
Automated substrate loading & unloading
Automated carrier return system
Controlled heating and cooling unit (CHU)
Dry air supply (CDA)
Carrier storage racks
Others on request

TECHNICAL DATA

Subject to change without notice due to technical improvement.

TARGET

Material metals, ceramics
Utilization planar > 25 %, rotatable > 75 %

SUBSTRATE

Material glass, polymers, silicon wafers
Dimensions (L x W), approx. 400 mm x 400 mm

DEPOSITION SYSTEM

Deposition type DC, pulsed DC, AC
Magnetron type planar, rotatable
Substrate temperature range RT / 200 °C
Substrate potential floating
Number of independent process gases 4 (e.g. Ar, Ar/O₂, N₂, O₂)

TRANSPORT

Type of transport inline, carrier-based
Orientation of substrate during deposition horizontal
Conveyor speed ≤ 1.5 m/min

VISS VERTICAL GLASS COATING SYSTEM

INDUSTRY-PROVEN PRODUCTION TOOL WITH A SMALL FOOTPRINT



The vertical inline sputter system **VISS** is an appropriate, modular solution for vertical deposition processes when scaling up from laboratory use to production. The tool is available either as a single end inline or for continuous processing and is uniquely suited for scaling up to substrate sizes of approximately 400 mm x 400 mm.

The substrates are transported by a carrier system, which is tilted vertically by seven degrees. The substrates can be loaded without touching their front side.



TECHNICAL DATA

Subject to change without notice due to technical improvement.

TARGET

Material metals, ceramics
Utilization planar > 25 %, rotatable > 75 %

SUBSTRATE

Material glass, polymers
Dimensions (L x W) approx. 400 mm x 400 mm

DEPOSITION SYSTEM

Deposition type DC, pulsed DC, AC
Magnetron type planar, rotatable
Substrate temperature range RT / 200 °C / 350 °C
Substrate potential floating
Number of independent process gases 4 (e.g. Ar, Ar/O₂, N₂, O₂)

TRANSPORT

Type of transport inline, carrier-based
Orientation of substrate during deposition vertical
Transport speed, max. ≤ 1.5 m/min

CLEANING OF CHAMBER

Cleaning principle mechanical exchange of shields
Cleaning cycle 7 to 25 days, depending on configuration

UTILITIES & SUPPLY

Power (phase/voltage/frequency) 3 AC/230 V, 400 V, 480 V/50 Hz, 60 Hz
Power consumption depending on configuration
Cooling system water cooling, separated cooling circuit
Cooling supply primary supply by customer
Venting system 1 system per lock chamber
Venting medium ambient air, compressed dry air
Process gases cabinets or central supply by customer

SYSTEM CONTROL & SOFTWARE

Computer hardware PLC, Siemens S7
User interface VON ARDENNE user interface
MES link according to specifications

SYSTEM DIMENSIONS

Total system size (L x W x H) depending on configuration
Total system weight depending on configuration

PIA|nova[®] HORIZONTAL GLASS COATING SYSTEM

INDUSTRY-PROVEN, RELIABLE STANDARD PRODUCTION TOOL



The **PIA|nova[®]** is our modular coating platform for solar applications. It allows VON ARDENNE to offer standard, yet flexible, manufacturing equipment for depositing thin films using physical vapor deposition (PVD) technology.

VON ARDENNE has incorporated its vast process know-how into this platform, gained from over 100 industry-proven glass and photovoltaic coating systems. The **PIA|nova[®]** is our answer to customers looking for productive and flexible production equipment combined with tried and tested technology and design.

HORIZONTAL SUBSTRATE TRANSPORT

The substrates are transported horizontally through the chambers combined with a sputter-down arrangement.



HEATING TECHNOLOGY

There are three fundamental process chamber types for processes:

- without heating (option to preheat)
- with heating up to 200 °C
- with heating up to 400 °C

CLEANING OF CHAMBER

Cleaning principle mechanical exchange of shields
Cleaning cycle 7 to 35 days, depending on configuration

UTILITIES & SUPPLY

Phase 3 phases
Voltage 230 V, 400 V, 480 V
Frequency 50 Hz to 60 Hz
Power consumption depending on configuration
Cooling system water cooling, separated cooling circuit
Cooling supply primary supply by customer
Venting system 1 system per lock chamber
Venting medium ambient air, compressed dry air or N₂
Process gases central supply by customer or local by gas cabinet

SYSTEM CONTROL & SOFTWARE

Computer hardware PLC, Siemens S7
User interface VON ARDENNE user interface
MES link according to specifications

SYSTEM DIMENSIONS

Total system size (L x W x H) customized x 9 m x 2.8 m
Total system weight depending on configuration

TECHNICAL DATA

Subject to change without notice due to technical improvement.

TARGET

Material metals, ceramics
Utilization planar > 30 %, rotatable > 80 %

SUBSTRATE

Material glass
Dimensions (L x W), max. 1 650 mm x 1 400 mm
Thickness 1.8 mm (1.4 mm) to 4 mm for glass

DEPOSITION SYSTEM

Deposition type DC, pulsed DC, AC
Magnetron type planar, single or dual rotatable
Sputter arrangement sputter down
Substrate temperature range RT / 200 °C / 400 °C
Substrate potential floating
Number of independent process gases up to 4 (Ar, O₂, N₂, X)

TRANSPORT

Type of transport inline
Orientation of substrate during deposition horizontal, LEL, SEL
Conveyor speed ≤ 3.5 m/min

GC120V VERTICAL GLASS COATING SYSTEM

INDUSTRY-PROVEN PRODUCTION TOOL WITH SMALL FOOTPRINT



The **GC120V** is a vertical inline coating system for the deposition of metal and oxide thin-film multilayer systems on flat glass substrates or other materials.

As a leading developer and manufacturer of vacuum coating equipment for large-area applications, VON ARDENNE has incorporated its broad knowledge and expertise in PVD technologies into the **GC120V** platform. The reliability of this system is well proven in the PV industry.

SMALL FOOTPRINT

Due to its vertical and carrier-based design, the **GC120V** does not need much floor space and requires fewer maintenance intervals.

GOOD MAINTAINABILITY

The optimized machine design enables easy access to the magnetron environment for target exchange and maintenance.

TECHNICAL DATA

Subject to change without notice due to technical improvement.

TARGET

Materials metals, ceramics
Utilization planar > 30 %, rotatable > 80 %

SUBSTRATE

Material glass
Dimensions (L x W), max. 1 550 mm x 1 200 mm (others on request)
Thickness 1.8 mm (1.4 mm) to 4 mm (others on request)

DEPOSITION SYSTEM

Deposition type DC, pulsed DC, AC
Magnetron type planar, single or dual rotatable
Sputter arrangement vertical
Substrate temperature range RT / 200 °C / 400 °C
Substrate potential floating
Number of independent process gases up to 4 (Ar, O₂, N₂, X)

TRANSPORT

Type of transport inline, carrier-based
Orientation of substrate vertical, LEL, SEL
Transport speed ≤ 3.5 m/min
Cycle time 30 s

CLEANING OF MAGNETRON CHAMBERS

Cleaning principle mechanical exchange of shields
Cleaning cycle 7 to 35 days, depending on configuration

UTILITIES & SUPPLY

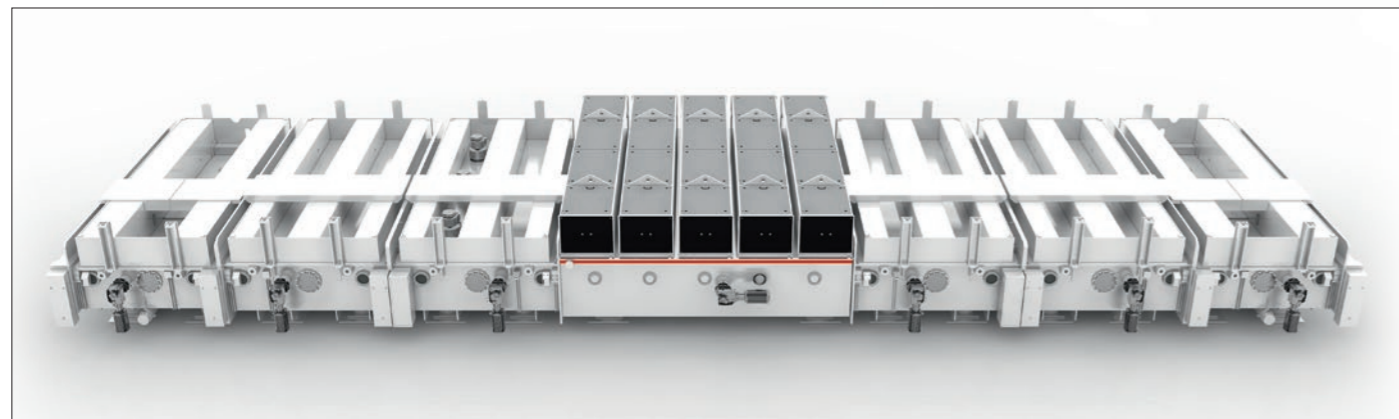
Automated substrate loading and unloading on request
Carrier storage racks on request
Phase 3 phases
Voltage 230 V, 400 V, 480 V
Frequency 50 Hz to 60 Hz
Power consumption depending on configuration
Cooling system separate cooling circuit with heat exchanger
Cooling supply primary cooling water supply by customer
Venting medium ambient air, compressed dry air or N₂
Process gases central supply by customer or local by gas cabinet

SYSTEM CONTROL & SOFTWARE

Computer hardware PLC, Siemens S7
User interface VON ARDENNE user interface
MES link according to specifications

SYSTEM DIMENSIONS

Total system size (L x W x H) customized x 13 m x 3.5 m
Total system weight depending on configuration



The **XENIA** is an inline coating system based on our proprietary large-area coating technology. As the coater is very wide and can therefore process many substrates at the same time, it is especially suited for high productivity applications at very low costs. It is suited for large-area glass substrates.

The **XENIA** benefits from our experience gained from delivering more than 150 coating systems to the photovoltaics industry. It is the perfect choice for customers looking for highly productive and flexible production equipment combined with proven technology and design.

HIGHEST ECONOMY OF SCALE

Due to its large width, the productivity of the tool is exceptionally high while the process utilization is brought to a maximum. Thus, the **XENIA** offers best cost of ownership by providing applicable economy of scale.

INDIVIDUAL PROCESS CHAMBERS

The process chamber can be equipped with five or more different process stations in a sputter down arrangement. It enables simultaneous processing of different material compositions from metallic and ceramic targets.

TECHNICAL DATA

Subject to change without notice due to technical improvement.

TARGET

Material: metals, ceramics
Utilization: planar > 30 %, rotatable > 80 %

SUBSTRATE

Material: glass
Dimensions (L x W), max.: 2000 mm x 2400 mm
Thickness: 1.8 mm (1.4 mm) to 4 mm

DEPOSITION SYSTEM

Deposition type: DC, pulsed DC, AC
Magnetron type: planar, single or dual rotatable
Sputter arrangement: sputter down
Substrate temperature range: RT / 200 °C / 400 °C
Substrate potential: floating
Number of independent process gases: up to 4 (Ar, O₂, N₂, X)

TRANSPORT

Type of transport: inline
Orientation of substrate during deposition: horizontal, LEL, SEL
Conveyor speed: ≤ 4.5 m/min

CLEANING OF MAGNETRON CHAMBERS

Cleaning principle: mechanical exchange of shields
Cleaning cycle: 7 to 35 days, depending on configuration

UTILITIES & SUPPLY

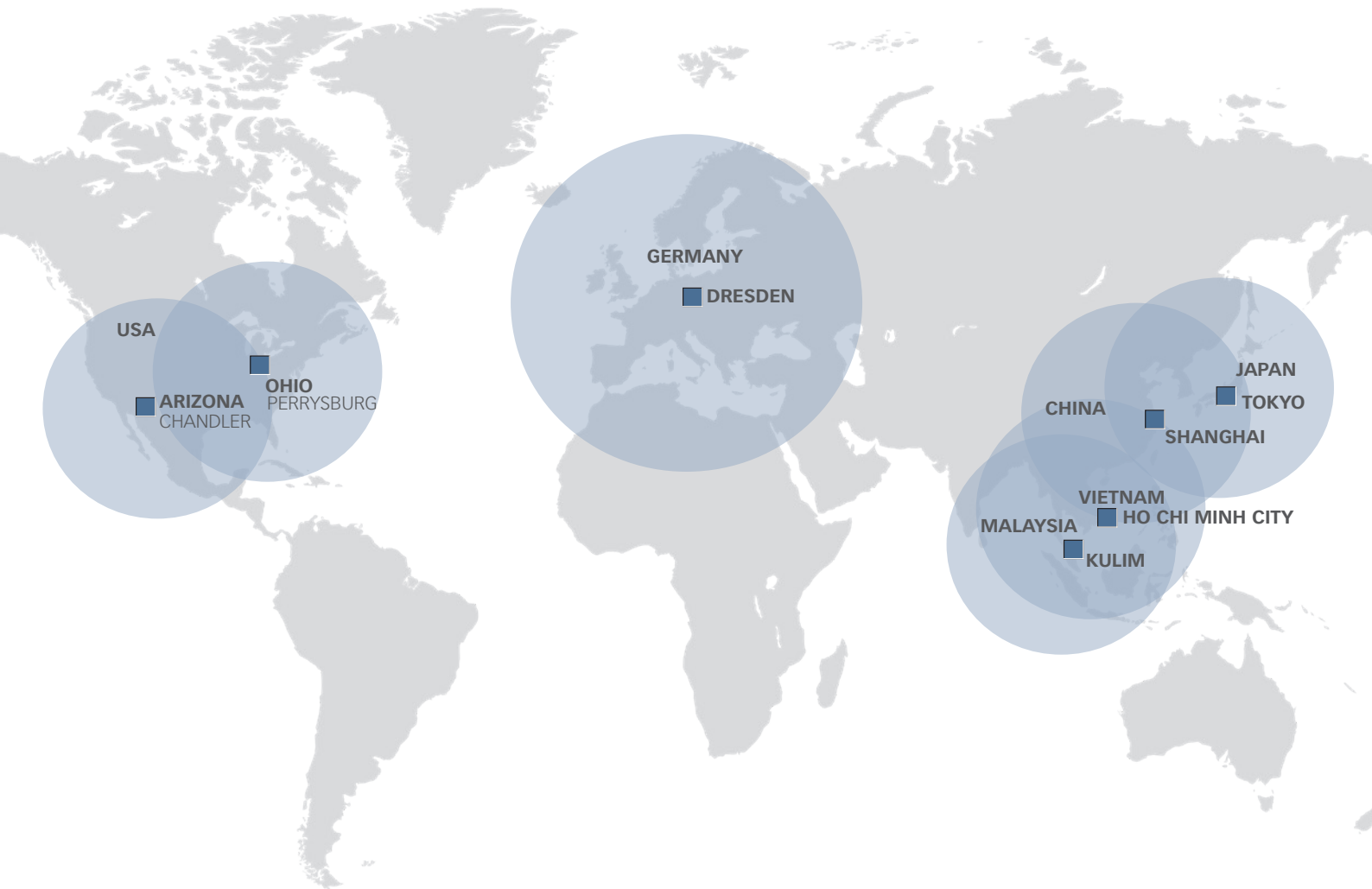
Phase: 3 phases
Voltage: 230 V, 400 V, 480 V
Frequency: 50 Hz to 60 Hz
Power consumption: depending on configuration
Cooling system: separate cooling circuit with heat exchanger
Cooling supply: primary cooling water supply by customer
Venting medium: ambient air, compressed dry air or N₂
Process gas: central supply by customer or local by gas cabinet

SYSTEM CONTROL & SOFTWARE

Computer hardware: PLC, Siemens S7
User interface: VON ARDENNE user interface
MES link: according to specifications

SYSTEM DIMENSIONS

Total system size (L x W x H): customized (min. 20 m) x 16.5 m x 3.5 m
Total system weight: depending on configuration



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KULIM



PRODUCT
TOPICS



PRODUCT
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COMPONENTS



www.vonardenne.biz

WHO WE ARE & WHAT WE DO

VON ARDENNE develops and manufactures industrial equipment for vacuum coatings on materials such as glass, wafers, metal strip and polymer films. These coatings give the surfaces new functional properties and can be between one nanometer and a few micrometers thin, depending on the application.

Our customers use these materials to make high-quality products such as architectural glass, displays for smartphones and touchscreens, solar modules and heat protection window film for automotive glass.

We supply our customers with technologically sophisticated vacuum coating systems, extensive expertise and global service. The key components are developed and manufactured by VON ARDENNE itself.

Systems and components made by VON ARDENNE make a valuable contribution to protecting the environment. They are vital for manufacturing products which help to use less energy or to generate energy from renewable resources.



SALES
CONTACTS



SERVICE
CONTACTS

WORLDWIDE SALES AND SERVICE

VON ARDENNE GmbH (headquarters) | Am Hahnweg 8 | 01328 DRESDEN | GERMANY

Sales: ☎ +49 (0) 351 2637 189 | ✉ sales@vonardenne.biz

Service: ☎ +49 (0) 351 2637 9400 | ✉ support@vonardenne.biz

VON ARDENNE Vacuum Equipment (Shanghai) Co., Ltd. | ☎ +86 21 6173 0210 | 📠 +86 21 6173 0200 | ✉ sales-vave@vonardenne.biz; support-vave@vonardenne.biz

VON ARDENNE Malaysia Sdn. Bhd. | ☎ +60 4408 0080 | 📠 +60 4403 7363 | ✉ sales-vama@vonardenne.biz; support-vama@vonardenne.biz

VON ARDENNE Japan Co., Ltd. | Tokyo office | ☎ +81 3 6435 1700 | 📠 +81 3 6435 1699 | ✉ sales-vajp@vonardenne.biz; support-vajp@vonardenne.biz

VON ARDENNE North America, Inc. | Ohio office | ☎ +1 419 386 2789 | 📠 +1 419 873 6661 | ✉ sales-vana@vonardenne.biz; support-vana@vonardenne.biz

VON ARDENNE North America, Inc. | Arizona office | ☎ +1 480 726 5470 | 📠 +1 480 855 0947 | ✉ sales-vana@vonardenne.biz; support-vana@vonardenne.biz

VON ARDENNE Vietnam Co., Ltd. | ☎ +60 124 23 7353 | ✉ sales-vavn@vonardenne.biz; support-vavn@vonardenne.biz